

## REMARKS

This application has been carefully reviewed in light of the April 4, 2005 Office Action. Claims 1 to 33 are in the application, with Claims 22 to 33 being withdrawn from consideration pursuant to a restriction requirement. Claims 1 and 11 are the independent claims under consideration. Claims 1, 3, 4, 7 to 11, 13, 14, and 17 to 20 have been amended. Reconsideration and further examination are respectfully requested.

Claims 1, 3, 4, and 12 to 14 were rejected under 35 U.S.C. § 112, second paragraph. The rejection is respectfully traversed, and is submitted to have been obviated by the amendments made to these claims.

Claims 1 to 23 were rejected for obviousness-type double patenting over Claims 1 to 18 of U.S. Patent No. 6,391,108 (Nishida). Applicants note that Nishida is available as prior art under 35 U.S.C. § 102(b). The rejection is respectfully traversed.

According to one feature of the invention as recited by Claims 1 and 11, a gas containing at least one of a raw material and a dopant is supplied to the solvent after at least a part of the gas is decomposed by application of energy to the gas.

Neither the disclosure of Nishida nor the claims of Nishida is seen to disclose this feature.

Nishida merely describes that the source gas is decomposed by injecting it into the solvent. See, for example, Claim 1 and col. 3, lines 47 to 50 of Nishida. Nishida does not describe that the source gas is decomposed by application of energy before supplying it to the solvent, as in the present invention.

The dependent claims are also submitted to be patentable because they set forth additional aspects of the present invention and are dependent from the independent

claims discussed above. Therefore, separate and individual consideration of each dependent claim is respectfully requested.

The application is believed to be in condition for allowance, and a Notice of Allowance is respectfully requested.

Applicants' undersigned attorney may be reached in our Costa Mesa, California office at (714) 540-8700. All correspondence should continue to be directed to our below-listed address.

Respectfully submitted,



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